Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
Li	502515	plasma	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:45
L2	91	((Na or K or sodium or potassium) adj hydroxide) and ((strip or stripping or stripper).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:24
L3	346	((Na or K or sodium or potassium) adj hydroxide) and ((clean or cleaning or cleaned or cleaner).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	-ON	2006/04/06 16:45
L4	2	((L2 or L3) and L1) and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:48
L5	2	L3 and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:49
L6	2	L3 and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:49
L7	2	(((Na or K or sodium or potassium) adj hydroxide) and ((clean or cleaning or cleaned or cleaner).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)) and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:51
L8	5	(((clean or cleaning or cleaned or cleaner).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)) and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:54

10	150	((alana au alagaine au alagaine)	LIC DCDUD	OB	ON	2006/04/06 16:55
L9	158	((clean or cleaning or cleaned or cleaner) and (photoresist or photopolymer or resist or semiconductor or eletronic)) and benzyltrimethylammonium	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:56
L10	61	((clean or cleaning or cleaned or cleaner) and (photoresist or photopolymer or resist or semiconductor or eletronic)) and (benzyltrimethylammonium adj hydroxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:00
L11	36	((strip or stripper or stripping) and (photoresist or photopolymer or resist or semiconductor or eletronic)) and (benzyltrimethylammonium adj hydroxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:09
L12	37	plasma and (photoresist or photopolymer or resist or semiconductor or eletronic) and (benzyltrimethylammonium adj hydroxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:20
L13	328	plasma and (benzyltrimethylammonium adj hydroxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:18
L14	291	13 not (11 or 12)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:20
L15	2368	benzyltrimethylammonium adj hydroxide	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:21
L16	1982	15 not (10 or 11 or 12 or 13)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:22

4/6/06 5:29:59 PM

L17	260742	(clean or cleanner or clean or cleaned or strip or striper or stripping) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:27
L18	0	16 and 17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:24
L19	2143073	(clean or cleanner or clean or cleaned or strip or striper or stripping)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:26
L20	260742	17 and 19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:26
L21	472	15 and 19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:27
L22	180	15 and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 17:27
S1	0	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide) same ((tetramethylene adj sulfone) or ((tetramethylene or tetramethyl) adj sulfone) or \$methylsulfone or \$methylenesulfone) same ((butyl adj ether) or butylether or diethyleneglycolbutylether or (dietheyleneglycol adj butyl adj ether) or (diethylene adj glycol adj butyl adj ether)) same \$mercaptobenzimidazole same (oxirane or octylphenylether or (octophenyl ether))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 13:37

4/6/06 5:29:59 PM

				·		
S2	0	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide) same ((tetramethylene adj sulfone) or ((tetramethylene or tetramethyl) adj sulfone) or \$methylsulfone or \$methylenesulfone) same ((butyl adj ether) or butylether or diethyleneglycolbutylether or (diethyleneglycol adj butyl adj ether) or (diethylene adj glycol adj butyl adj ether)) same \$mercaptobenzimidazole	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 13:39
S3	0	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide) same ((tetramethylene adj sulfone) or ((tetramethylene or tetramethyl) adj sulfone) or \$methylenesulfone or \$methylenesulfone) same ((butyl adj ether) or butylether or diethyleneglycolbutylether or (diethyleneglycol adj butyl adj ether) or (diethylene adj glycol adj butyl adj ether))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR -	ON	2006/04/05 13:39
S4	0	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide) same ((butyl adj ether) or butylether or diethyleneglycolbutylether or (dietheyleneglycol adj butyl adj ether) or (diethylene adj glycol adj butyl adj ether))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 13:40
S5	4	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:21
S6	33	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same ((k or potassium or Na or sodium) adj hydroxide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 13:47

			T	I		
S7	29	S6 not S5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 13:48
S8	87	(clean or cleanner or clean or cleaned) same (\$methylammonium adj hydroxide) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 14:04
S9	83	S8 not S6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 14:04
S10	362	(clean or cleanner or clean or cleaned) same ((k or potassium or Na or sodium) adj hydroxide) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 14:25
S11	1	(clean or cleanner or clean or cleaned) same (\$methylammonium adj3 (k or potassium or Na or sodium)) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:30
S12	0	(clean or cleanner or clean or cleaned) same ((k or potassium or Na or sodium) adj \$methylammonium) same (photoresist or resist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:26
S13	0	(clean or cleanner or clean or cleaned) same ((k or potassium or Na or sodium) adj3 \$methylammonium) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:26
S14	2	(clean or cleanner or clean or cleaned) same (\$methylammonium adj3 (k or potassium or Na or sodium))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:28

S15	2	(clean or cleanner or clean or cleaned) same (\$methylammonium adj3 (k or potassium or Na or sodium))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:29
S16	90	(\$methylammonium adj3 (k or potassium or Na or sodium)) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:37
S17		((k or potassium or Na or sodium) adj2 \$methylammonium) same (photoresist or resist or photoresist or photopolymer or sacrifical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR .	ON	2006/04/05 15:45
S18	1917	((k or potassium or Na or sodium) adj2 \$methylammonium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:46
S19	391	((k or potassium or Na or sodium) adj \$methylammonium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/05 15:58
S20	97	\$methylammonium adj (k or potassium or Na or sodium)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 07:22
S21	4	\$methylammonium adj (k or potassium or Na or sodium) and strip	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 07:26
S22	5	\$methylammonium adj (k or potassium or Na or sodium) and (strip or stripping or stripper)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 07:28

S23	2067	\$methylammonium adj hydroxide and (strip or stripping or stripper)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 07:29
S24	1099	\$methylammonium adj hydroxide and (strip or stripping or stripper) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 07:31
S25	1099	\$methylammonium adj hydroxide and (strip or stripping or stripper) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 09:20
S26	91	((Na or K or sodium or potassium) adj hydroxide) and ((strip or stripping or stripper).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 09:23
S27	346	((Na or K or sodium or potassium) adj hydroxide) and ((clean or cleaning or cleaned or cleaner).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 09:23
S28	435	S26 or S27	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 12:21
S29	502515	plasma	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 12:21
S30	91	((Na or K or sodium or potassium) adj hydroxide) and ((strip or stripping or stripper).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 12:21

S31	346	((Na or K or sodium or potassium) adj hydroxide) and ((clean or cleaning or cleaned or cleaner).ti.) and (photoresist or photopolymer or resist or semiconductor or eletronic)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:50
S32	79	(S30 or S31) and S29	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/04/06 16:44